

Title (en)
DEVICE FOR VERY HIGH FREQUENCY PLASMA ASSISTED CVD UNDER ATMOSPHERIC PRESSURE, AND APPLICATIONS THEREOF

Title (de)
VORRICHTUNG ZUR PLASMAUNTERSTÜTZTEN CHEMISCHEN GASPHASENABSCHEIDUNG MIT HOHER FREQUENZ UNTER
ATMOSPHÄRISCHEM DRUCK SOWIE ANWENDUNGEN DAFÜR

Title (fr)
DISPOSITIF ET PROCEDE DE DEPOT CVD ASSISTE PAR PLASMA TRES HAUTE FREQUENCE A LA PRESSION ATMOSPHERIQUE, ET SES
APPLICATIONS

Publication
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Application
EP 08837638 A 20080916

Priority
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Abstract (en)
[origin: WO2009047442A1] The invention relates to a method for CVD on a substrate under atmospheric pressure, characterised in that it is assisted by a very-high-frequency plasma generated by a field applicator with an elongated conductor of the micro-ribbon or hollow conducting line type. The invention also relates to the use thereof for applying an electrically conductive inorganic layer on elements of vehicle bodywork, particularly the bumpers.

IPC 8 full level
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Citation (search report)
See references of WO 2009047442A1

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